

LA-UR-22-29768

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Title: Stoichiometry control and automated growth of alkali antimonide photocathode films by molecular beam deposition

Author(s): Pavlenko, Vitaly

Intended for: European Workshop on Photocathodes for Particle Accelerator Applications (EWPAA 2022), 2022-09-20/2022-09-22 (Milano, Italy)

Issued: 2022-09-20



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Stoichiometry control and automated growth of alkali antimonide photocathode films by molecular beam deposition

Vitaly Pavlenko

*European Workshop on Photocathodes for Particle Accelerator Applications
Milano, Italy
September 22, 2022*

This presentation is based on:

Applied Physics Letters

ARTICLE

scitation.org/journal/apl

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Appl. Phys. Lett. **120**, 091901 (2022);
<https://doi.org/10.1063/5.0080948>

Cite as: Appl. Phys. Lett. **120**, 091901 (2022); doi: [10.1063/5.0080948](https://doi.org/10.1063/5.0080948)

Submitted: 5 December 2021 · Accepted: 10 February 2022 ·

Published Online: 1 March 2022






View Online



Export Citation



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Vitaly Pavlenko,^{a)}  John Smedley,  Alexander Scheinker,  Ryan L. Fleming,  Anna Alexander, 
Mark A. Hoffbauer,  and Nathan A. Moody 

AFFILIATIONS

Los Alamos National Laboratory (LANL), P.O. Box 1663, Los Alamos, New Mexico 87545, USA

^{a)} Author to whom correspondence should be addressed: pavlenko@lanl.gov

ABSTRACT

We report on a method of photoemissive film growth that controls stoichiometry in real time. We show that stoichiometry control using a

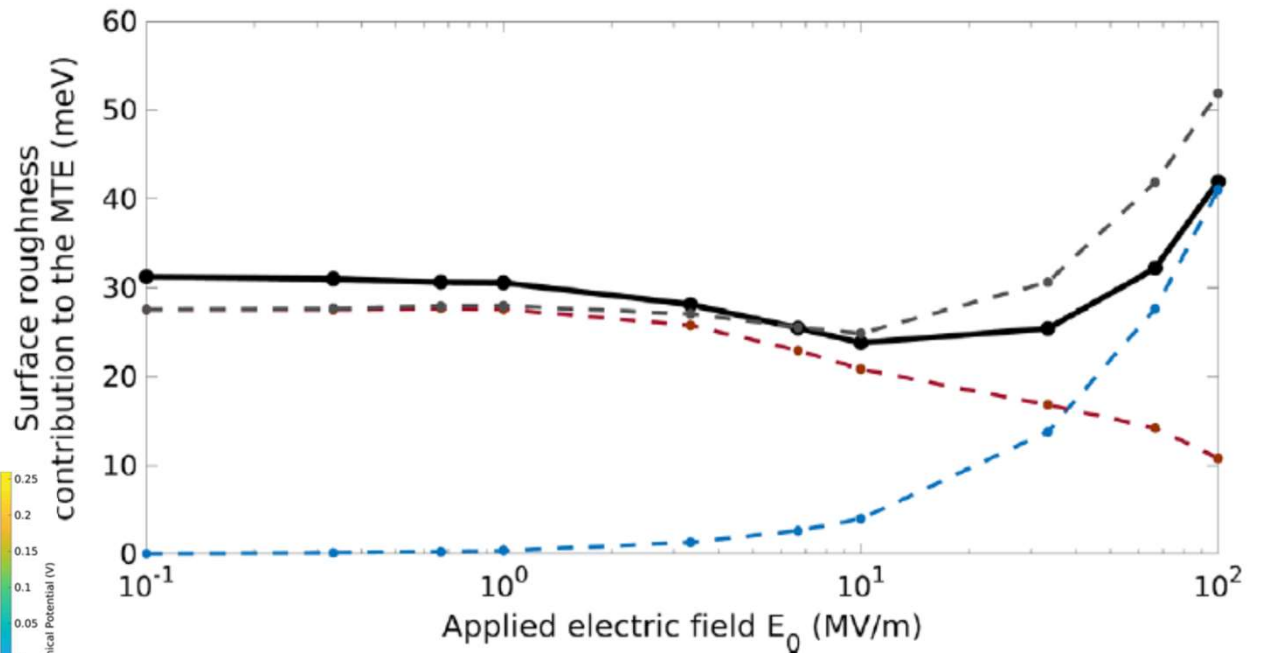
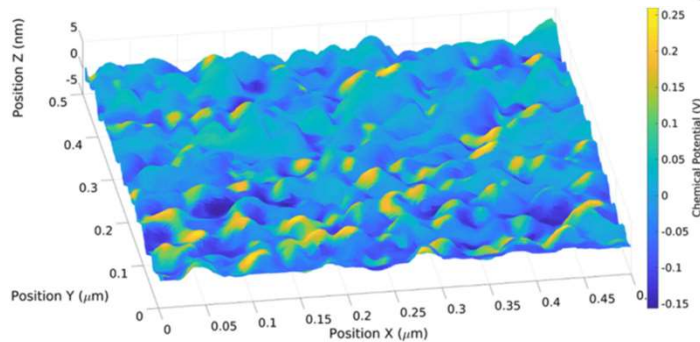
Acknowledgements

- Team: **John Smedley (now SLAC)**
Alexander Scheinker
Ryan L. Fleming
Anna Alexander
Mark A. Hoffbauer
Nathan A. Moody
- Tech support: **Fangze Liu and Anju Poudel**
- Discussions: **Dimitre Dimitrov, Enrique Batista, and John Lewellen (now SLAC)**
- Funding: **Laboratory Directed Research and Development program of LANL, projects 20190536ECR, 20210595DR, and 20220058ER.**



INTRO: Roughness is always bad for MTE

$kT +$



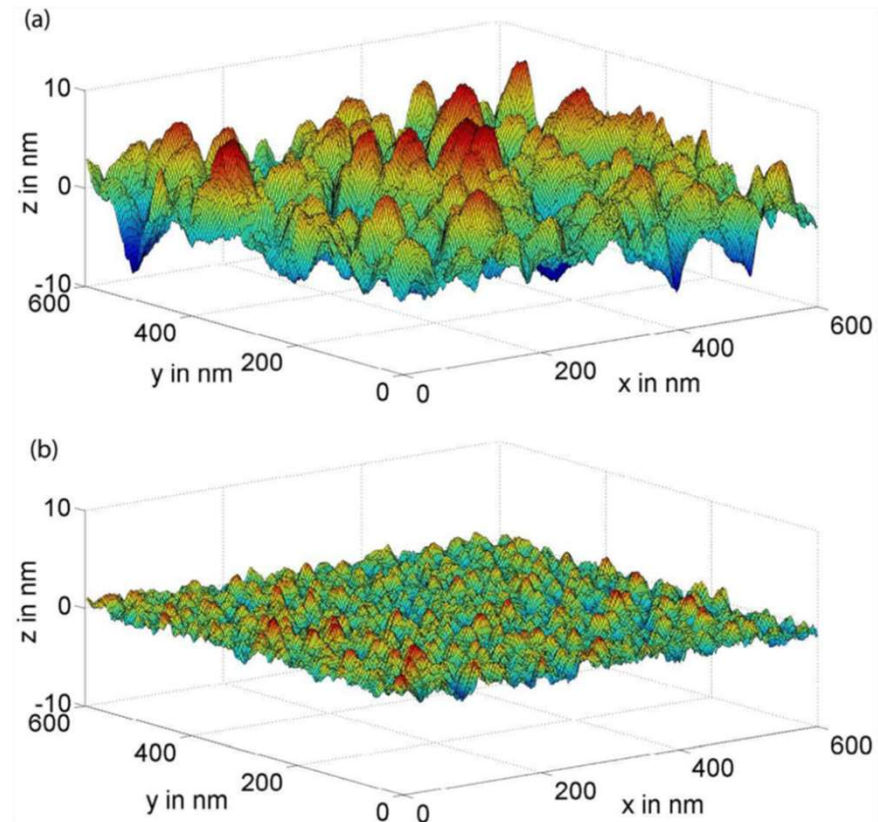
From: G. S. Gevorkyan, S. Karkare, S. Emamian, I. V. Bazarov, and H. A. Padmore, Effects of physical and chemical surface roughness on the brightness of electron beams from photocathodes, Phys. Rev. Accel. Beams **21**, 093401 (2018)

INTRO: Co-deposition produces smoother films

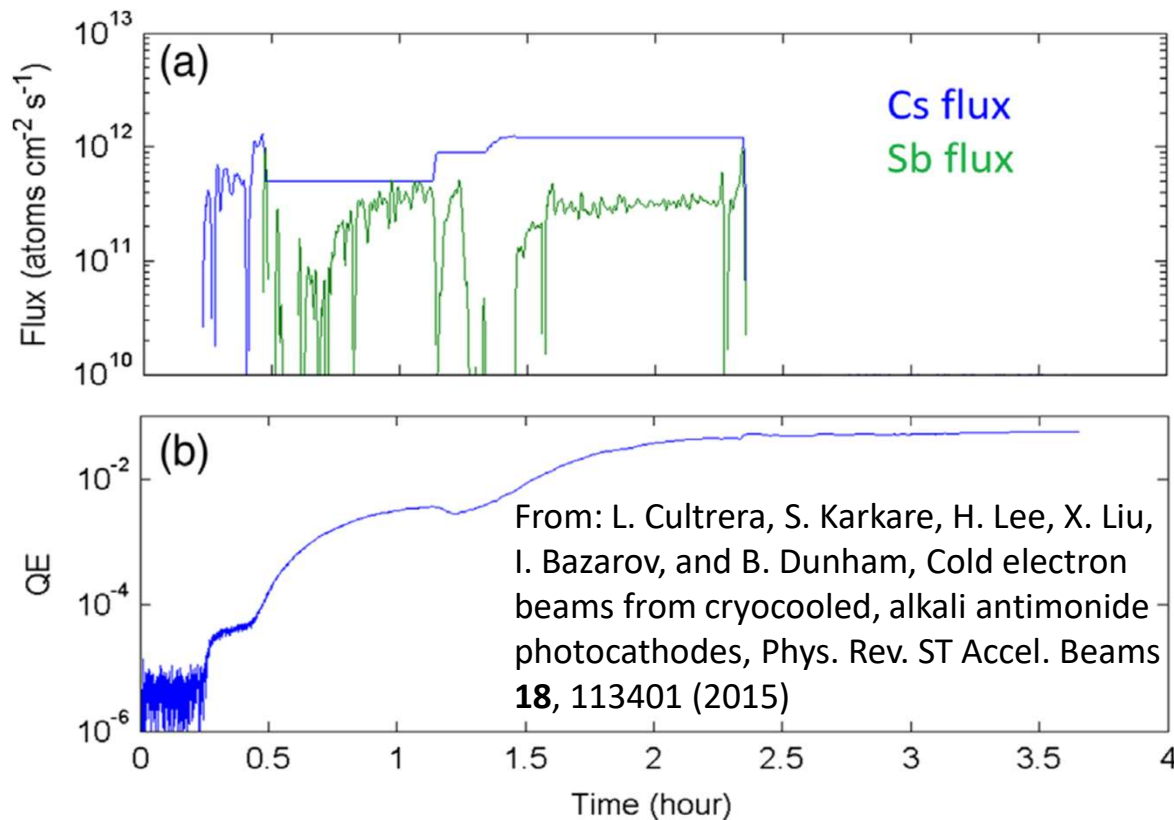
From: Jun Feng,
Siddharth Karkare,
James Nasiatka,
Susanne Schubert,
John Smedley, and
Howard Padmore, Near
atomically smooth alkali
antimonide
photocathode thin films,
Journal of Applied
Physics **121**, 044904
(2017)

sequential
deposition

CO-
deposition



INTRO: Real-world co-deposition of mono-alkalis

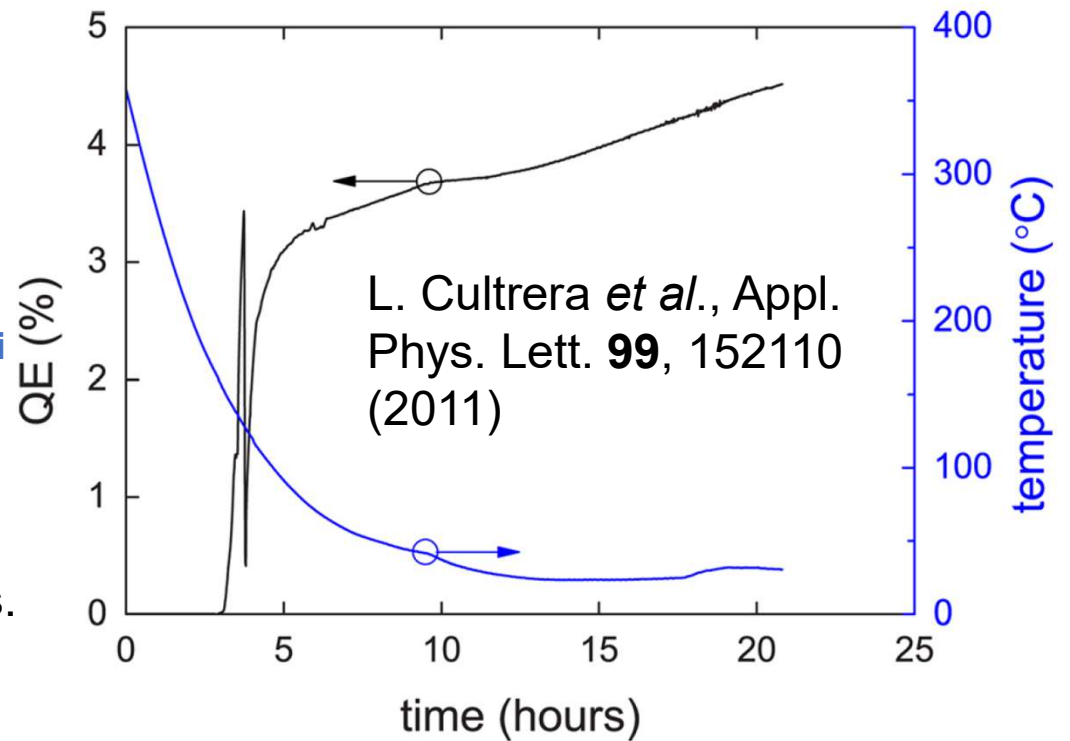
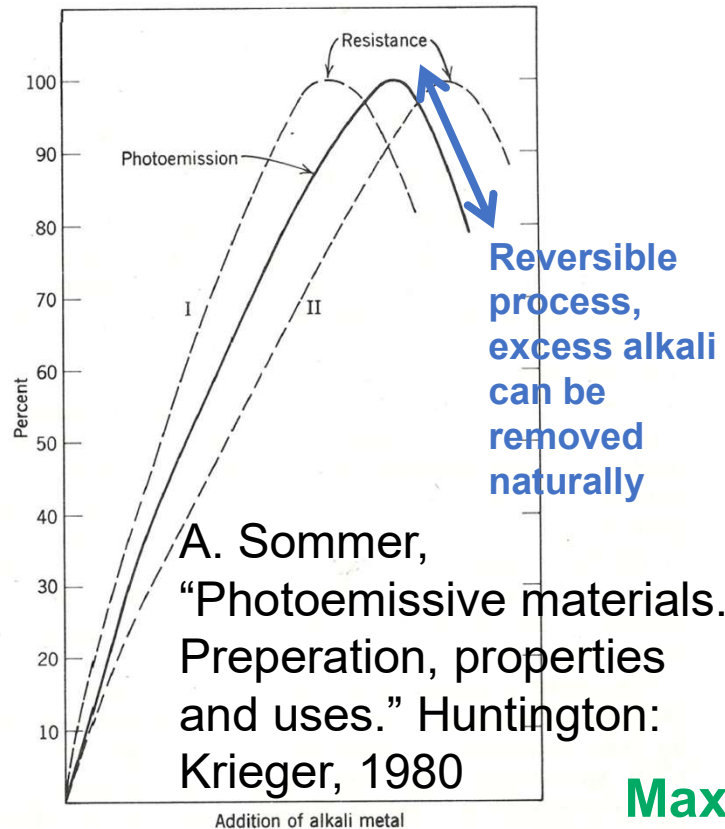


Fluxes are being adjusted, what is the algorithm?

“... many growers adjust their reactant fluxes to maximize the quantum efficiency (QE) of the growing photocathode at a convenient wavelength.”

From: Alice Galdi, William J. I. DeBenedetti, Jan Balajka, Luca Cultrera, Ivan V. Bazarov, Jared M. Maxson, and Melissa A. Hines, The effects of oxygen-induced phase segregation on the interfacial electronic structure and quantum efficiency of Cs₃Sb photocathodes, J. Chem. Phys. **153**, 144705 (2020)

INTRO: What does maximizing QE mean?



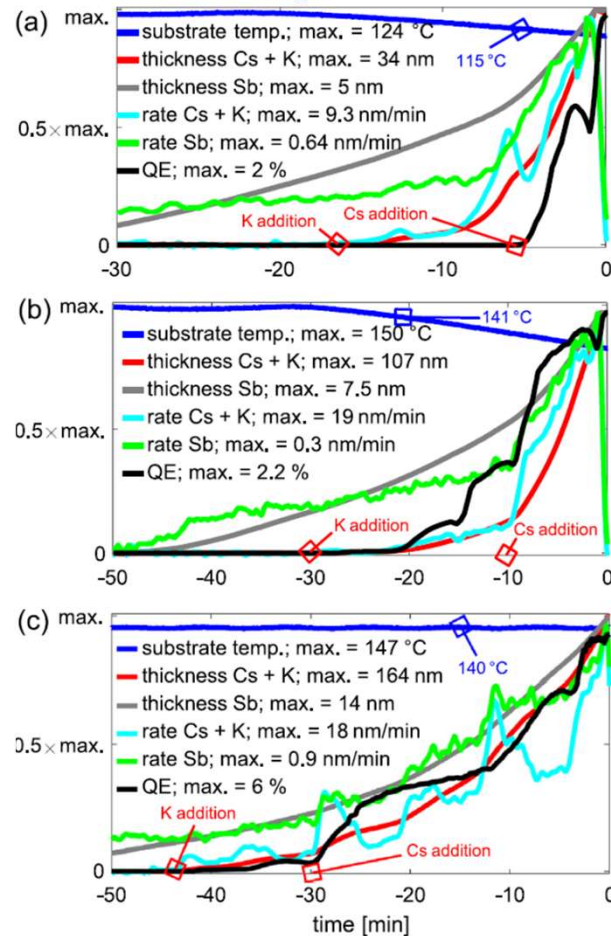
Max QE = Stable “Stoichiometric” Compound

But QE is a function of film thickness

Figure 21. Variation of resistance and photoemission during formation of alkali antimonide photocathodes: curve I for *n*-type materials and curve II for *p*-type materials.

INTRO: Real-world co-deposition of bi-alkalis

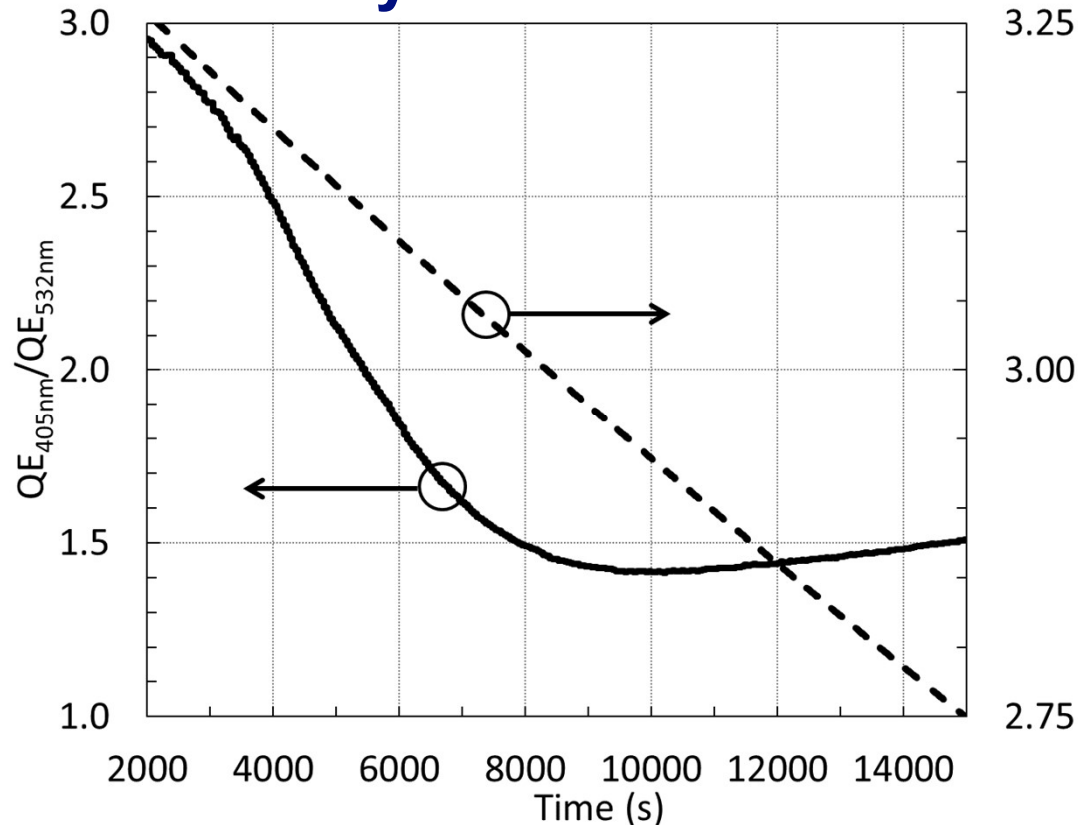
From: H. Panuganti, E. Chevally, V. Fedosseev, M. Himmerlich, Synthesis, surface chemical analysis, lifetime studies and degradation mechanisms of Cs-K-Sb photocathodes, Nuclear Inst. and Methods in Physics Research, A **986** (2021) 164724



Algorithm description:
“slope of the *in situ* photocurrent as the driver for the growth process”

Human-mediated algorithms typically do not work well.

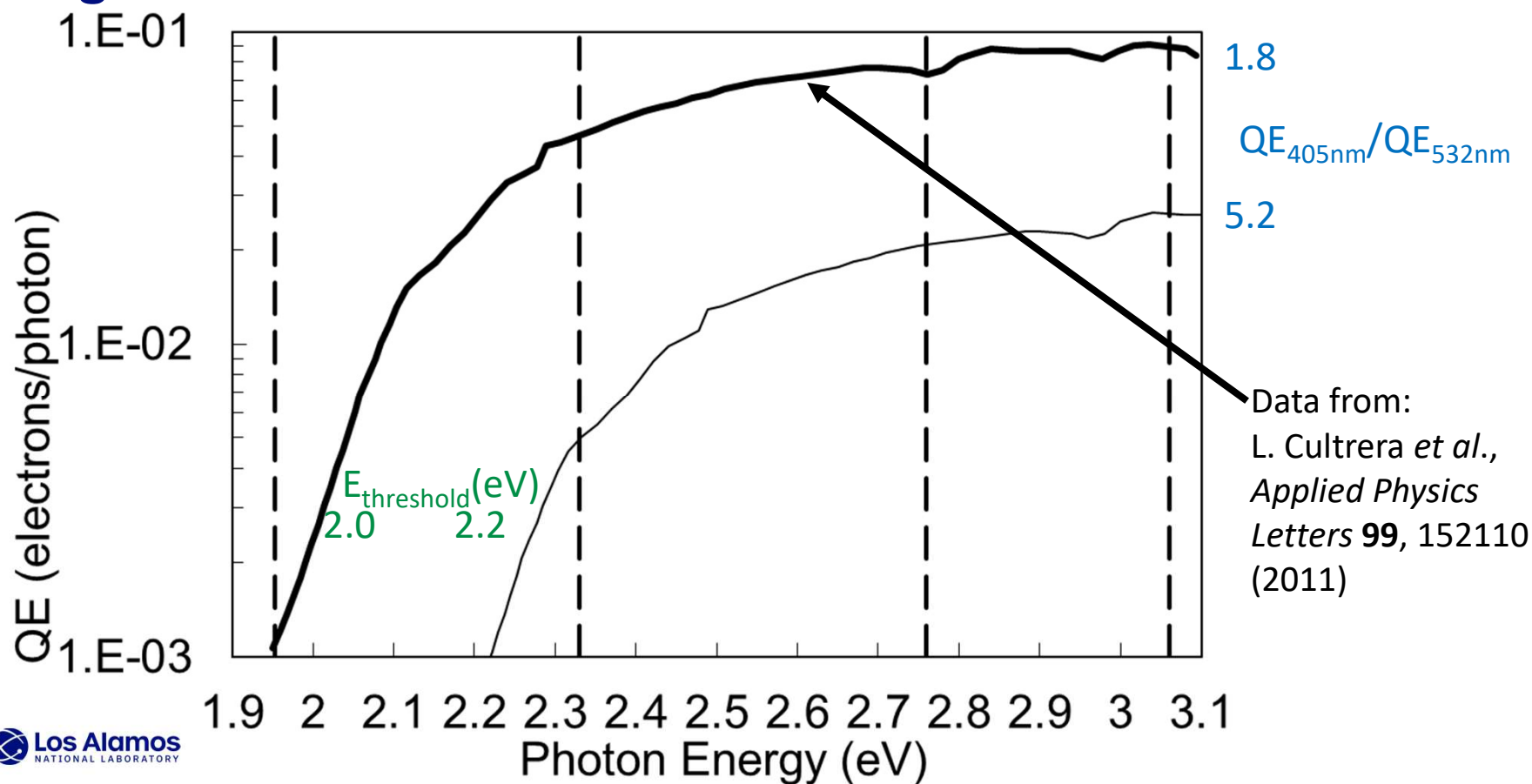
Thickness-independent photoemission parameter(s) vs stoichiometry



Corroboration: excess Cs removal experiments & thermal decomposition experiments

- Time axis effectively represents stoichiometry
- Cs/Sb atomic flux ratio close to 3 for low substrate temperature
- Minimum of QE_{405nm}/QE_{532nm} approximately coincides with QE maximum
- To facilitate process control, need to remain is Cs-rich growth mode, otherwise need *elaborate extremum seeking*

Why does QE_{405nm}/QE_{532nm} change when stoichiometry changes?

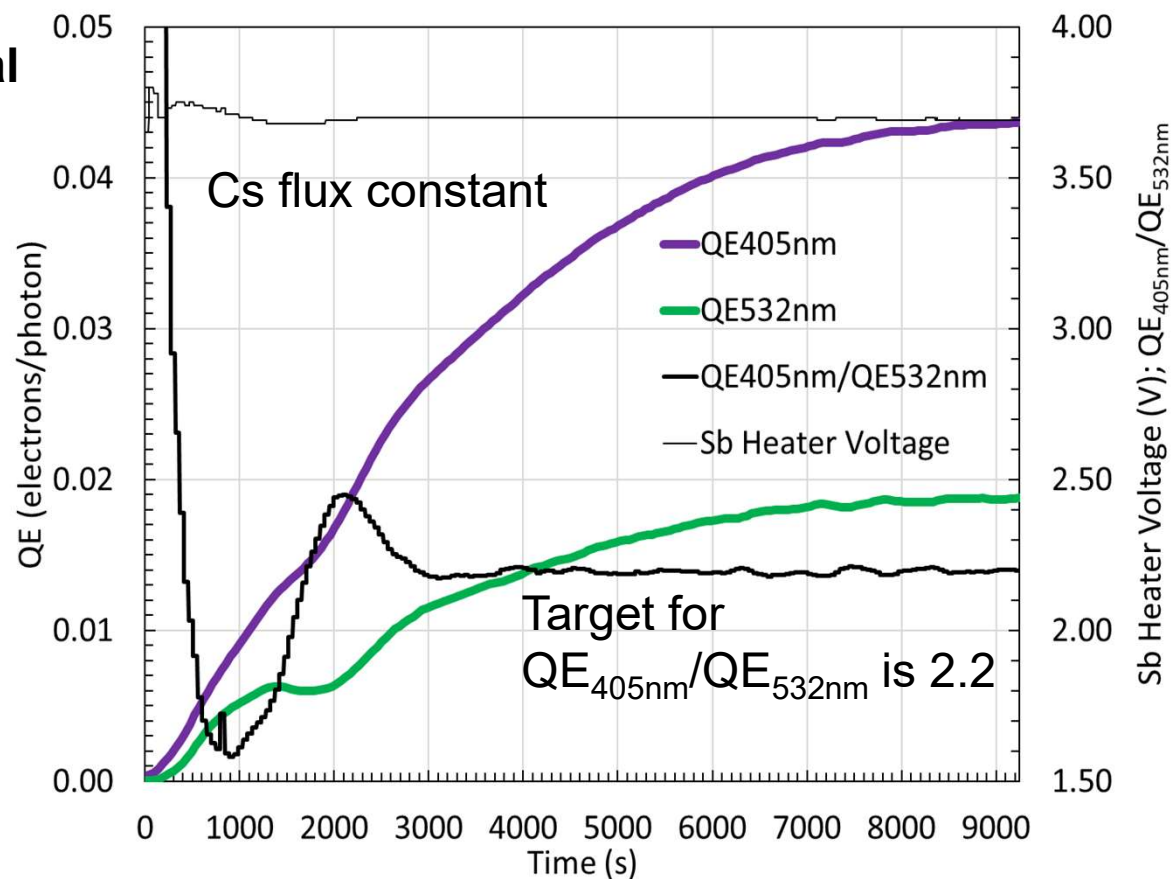


Process control: stabilizing thickness-independent photoemission parameter

Feedback loop is an essential part of process control.

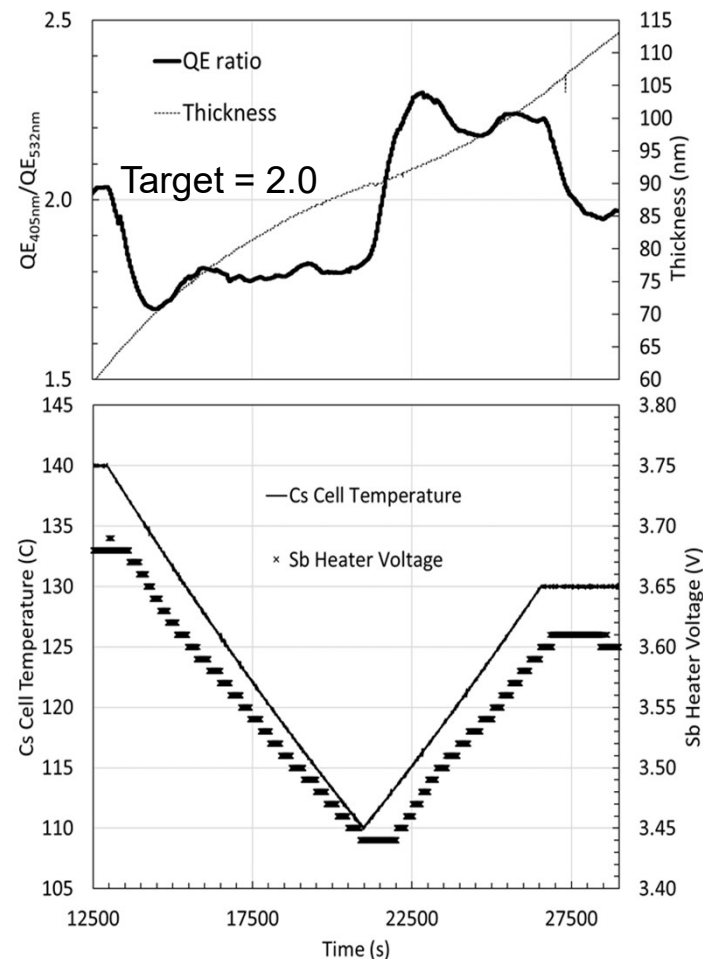
PREREQUISITES:

- Reasonably stable calibrated sources
- Cs-rich growth mode
- Software PID feedback loop with pre-determined gains (Ziegler-Nichols method) or other properly tuned algorithm



Process control: stress test

Sb flux
“chasing”
Cs flux



- Sb flux keeps up with Cs flux!
(Sb flux “knows” nothing about Cs flux value or derivative, it is merely a function of film’s photoemission)
- Time lag is about 500 s, including significant instrumental factor
- Ratio of fluxes and stoichiometry (both inferred) are maintained with a few % precision
- Max/min growth rate here is about 2.5, practically achievable range much larger
- Excellent tool for more accurate estimates of starting fluxes

Thin film growth recipes that we can share

- **Recipes for photoemissive materials**
 - Substrate temperature (low, difficult to calibrate but solvable)
 - Growth rate (proxy such as Sb flux), including **variable**
 - Stoichiometric offset(s) based on photoemission

Calibration uncertainties do not matter too much.

Accurate QE measurements do not require cross-calibration between the labs.

Future Plans: Technology Maturation and Transfer

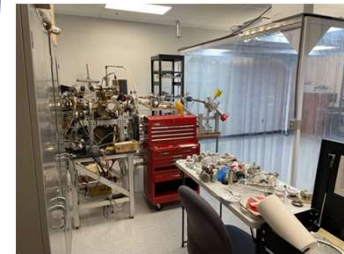


automated photocathode growth technology

Radiation Monitoring Devices, Inc. (RMD)



Sputter deposition
tech & targets



Thank you for your attention!

Questions?